

## $\alpha,\omega$ -dihexyl-sexithiophene thin films for solution-gated organic field-effect transistors

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While organic semiconductors are being widely investigated for chemical and biochemical sensing applications, major drawbacks such as the poor device stability and low charge carrier mobility in aqueous electrolytes have not yet been solved to complete satisfaction. In this work, solution-gated organic field-effect transistors (SGOFETs) based on the molecule  $\alpha,\omega$ -dihexyl-sexithiophene (DH6T) are presented as promising platforms for in-electrolyte sensing. Thin films of DH6T were investigated with regard to the influence of the substrate temperature during deposition on the grain size and structural order. The performance of SGOFETs can be improved by choosing suitable growth parameters that lead to a two-dimensional film morphology and a high degree of structural order. Furthermore, the capability of the SGOFETs to detect changes in the pH or ionic strength of the gate electrolyte is demonstrated and simulated. Finally, excellent transistor stability is confirmed by continuously operating the device over a period of several days, which is a consequence of the low threshold voltage of DH6T-based SGOFETs. Altogether, our results demonstrate the feasibility of high performance and highly stable organic semiconductor devices for chemical or biochemical applications. ©  $2016\ AIP\ Publishing\ LLC$ . [http://dx.doi.org/10.1063/1.4942407]

Organic semiconductors offer the possibility to fabricate devices featuring biocompatibility, 1,2 mechanical flexibility, 3-5 and comparably low production costs. 1,2 Therefore, a wide range of applications employing organic semiconductors is being currently explored in the fields of biosensing and biomedical technologies. 6-8 Among other molecules, oligothiophenes have been studied intensively for their suitability to be applied in field-effect transistors. 9-17 In the case of solution-gated organic field-effect transistors (SGOFETs), the organic semiconductor is gated through an electrolyte. An electrical double layer, characterized by a rather high interfacial capacitance, builds up at the semiconductor-liquid interface. Consequently, the applied gate bias voltage may be kept well under 1 V, 18-20 leading to an improved device stability and the possibility of in-electrolyte applications.  $^{8,16,17,21,22}$  Using  $\alpha$ -sexithiophene (6T) as active material, biofunctional sensors for the detection of penicillin have been demonstrated previously.<sup>17</sup> However, the stability of the device strongly depends on the characteristics of the employed organic molecules. It is, therefore, of utmost importance to explore the use of molecules which could eventually lead to an improved device stability.

In this work, we report on the implementation of the end-substituted molecule  $\alpha,\omega$ -dihexyl-sexithiophene (DH6T) in SGOFETs. DH6T has been reported to exhibit favorable properties like an improved structural order in thin films and

an increased field-effect mobility as compared to the unsubstituted 6T.<sup>23,24</sup> Here, we demonstrate the influence of the substrate temperature during deposition on the morphology and structural order of the thin film by atomic force microscopy (AFM), X-ray reflectivity (XRR), and UV-Vis spectroscopy. Furthermore, we characterize SGOFETs based on DH6T with regard to transistor performance and stability, and we reveal their sensitivity towards changes in the pH and ionic strength of the gate electrolyte.

Organic thin films of DH6T (nominal thickness: 30 nm) were deposited on sapphire substrates by organic molecular beam deposition in an ultrahigh vacuum system as described previously. 16,17 In order to tune the morphology of the deposited films, the temperature of the sapphire substrate  $T_{sub}$  during thin film deposition was varied between room temperature (19 °C) and 55 °C. Typical deposition rates are between 0.5 and 2 Å/min. The fabrication details of the SGOFETs (width-to length ratio of the transistor channel: W/L = 4900) have been described elsewhere 16,17 and remained unchanged in this work, except for the contact thickness (5 nm Ti/45 nm Au). All measurements were carried out in ambient atmosphere. The transistor and stability characterization and the ion sensing experiments were performed in a 5 mM phosphate buffered saline (PBS) solution at pH 5. To change the ionic strength, KCl solution was added to the buffer. For the pH sensing measurements, a 10 mM PBS solution, whose ionic strength was adjusted to 50 mM with KCl (KPBS), was used. The pH was altered by adding either HCl or KOH solution. The gate voltage was applied via an Ag/AgCl reference electrode in all cases.

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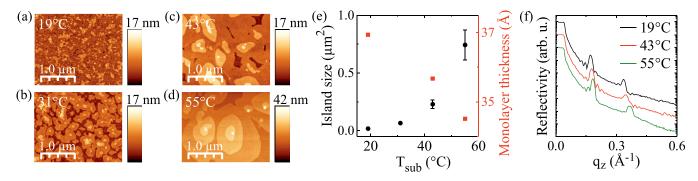


FIG. 1. Characterization of nominally 30 nm thick DH6T thin films deposited at different substrate temperatures. (a) AFM micrographs for  $T_{sub} = 19$  °C (room temperature), (b)  $T_{sub} = 31$  °C, (c)  $T_{sub} = 43$  °C, and (d)  $T_{sub} = 55$  °C. (e) Average size of the grains versus  $T_{sub}$  as extracted from AFM images (black dots) and monolayer thickness in the thin films (red squares) as a function of  $T_{sub}$ . The latter was calculated from the position of the first order peak in the X-ray reflectivity spectra of the deposited DH6T films (f).

The temperature of the sapphire substrate  $T_{sub}$  was varied and its influence on the morphology of the DH6T layers was investigated. As the AFM micrographs in Figures 1(a)–1(d) illustrate, the grains are larger and exhibit a more three-dimensional topography for higher temperatures. This is understood in terms of an extended diffusion length of molecules with rising temperatures on the substrate surface. A quantitative analysis of the average island size for different values of  $T_{sub}$  is shown in Figure 1(e) (black dots).

To investigate possible changes in the thin film structure itself, XRR spectra were recorded for films deposited at different  $T_{sub}$  (see Figure 1(f)). Garnier et al. have reported a monoclinic unit cell in DH6T thin films with an angle  $\beta = 111.3^{\circ}$  and a tilt angle between core and side chains of 16°, leading to an effective molecule length of 38.1 Å.<sup>23</sup> The theoretical value of the monolayer thickness thereby calculates to 35.5 Å. From the position of the first order peak,  $q_1$ , the monolayer thickness d of the investigated thin films can be calculated via  $d = 2\pi/q_1$ . As illustrated in Figure 1(e) (red squares), it lies in the expected range; however, a decrease in the monolayer thickness with increasing  $T_{sub}$  is observed, which may be due to a change in the tilt angle of the DH6T molecules towards the substrate surface normal. In addition, the first order peak in the XRR spectra becomes more intense with increasing substrate temperature (see Figures S1(a) and S1(b) (Ref. 26)), indicating a higher degree of structural order in these thin films, as discussed in the following.

Additional information related to the structural order can be obtained from UV-Vis spectroscopy. Absorption spectra of DH6T thin films deposited at various  $T_{sub}$  are depicted in Figure 2(a). These are normalized to the intensity of the most prominent peak at about 3.3 eV, which corresponds to the HOMO -> LUMO transition of molecules for which the interaction with neighboring molecules leads to a Davydov splitting of the LUMO.<sup>27,28</sup> This absorption peak is most intense and narrow, if the transition dipoles of all molecules are aligned in parallel. The normalized spectra illustrate a change in the shape of this peak with  $T_{sub}$ , suggesting a change in the interaction between molecules in the thin film. The quantitative analyses of the average peak intensity and full width at half maximum (FWHM) (Figure 2(b)) reveal an increase in the peak intensity and a decrease in the FWHM with increasing  $T_{sub}$  (see Figure S2(a) for nonnormalized spectra<sup>26</sup>). These findings indicate an increase in the degree of structural order of the thin films for higher substrate temperatures, in agreement with the XRR data presented above. In contrast, no dependence on  $T_{sub}$  was found for the intensity of the peak at 4.3 eV (see Figure S2(b) (Ref. 26)). Such a peak has already been observed for thin films of oligothiophenes of various conjugation core lengths and with different substituents and is attributed to the absorption of a single thiophene unit.<sup>29</sup> Its independence of  $T_{sub}$  originates from the molecular character of the corresponding transition, as opposed to the crystalline HOMO  $\rightarrow$  LUMO transition located at 3.3 eV.

DH6T thin films were used as the active material in SGOFETs, the layout of which is sketched in Figure 3(a). The Ti/Au contact pattern was predefined by photolithography, deposited via thermal evaporation and partly covered by a photoresist prior to the organic thin film growth. Exemplary transistor output curves in a 5 mM PBS buffer at pH 5 are shown in Figure 3(b). They show a current level of several  $10 \,\mu\text{A}$  and saturation behavior for high drain-source voltages. Furthermore, the gate-source current is three orders of magnitude smaller than  $I_{DS}$ , and cyclic voltammetry measurements show no indication of Faradaic processes in the potential window of the SGOFETs (see Figures S3(a) and 3(b) (Ref. 26)). Therefore, we can conclude that the current modulation is dominated by the field-effect, in agreement with previous reports. 20,30 From the transfer curve at a drainsource voltage  $U_{DS} = -50 \,\mathrm{mV}$  (black dots in Figure 3(c)), a

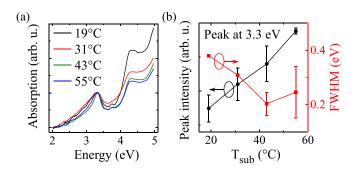


FIG. 2. Optical characterization by UV-Vis spectroscopy of 30 nm thick DH6T films deposited at different substrate temperatures. (a) Absorption spectra, normalized by the intensity of the peak at  $3.3 \,\mathrm{eV}$ . (b) Average intensity (black dots) and FWHM (red squares) of the same peak as a function of  $T_{sub}$ . The lines were added as a visual guidance. The error bars represent the standard error of the mean values.

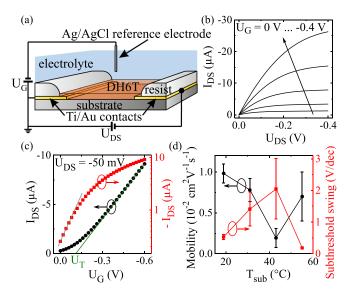


FIG. 3. Electrical characterization of SGOFETs using 30 nm thick films of DH6T as the active material. The measurements were conducted in 5 mM PBS at pH 5. (a) Device layout. The width-to-length ratio is 4900. (b) Typical output characteristics and (c) corresponding transfer curve at  $U_{DS} = -50 \,\mathrm{mV}$  on a linear (black dots) and logarithmic scale (red squares). Linear fits to the data are represented by the solid lines and the threshold voltage  $U_T$  is indicated. The DH6T thin film of this sample was deposited at  $T_{sub} = 19\,^{\circ}\mathrm{C}$ . (d) Field-effect mobility (black dots) and subthreshold swing (red squares) versus  $T_{sub}$  as extracted from the transfer curves. The lines were added as a visual guidance. The error bars represent the standard error of the mean values (see supplementary material  $^{26}$ ).

transconductance  $g_m = 18 \,\mu\text{S}$  was obtained, which can be used to determine the field-effect mobility  $\mu$  via  $\mu = g_m/$  $(C_{dl}U_{DS})$  L/W. In this equation,  $C_{dl}$  is the electrical double layer capacitance of the semiconductor-electrolyte interface, which was estimated to  $4 \mu F/cm^2$  via electrochemical impedance spectroscopy (see Figure S4 (Ref. 26)). This compares well to the interfacial capacitances of other solution-gated organic field effect transistor systems. 16,31,32 From the maximum transconductance of the devices, we can estimate a field-effect mobility of up to about  $1 \times 10^{-2}$  cm<sup>2</sup>/V s for the discussed set of transistors (Figure 3(d)) and of up to  $1.9 \times 10^{-2}$  cm<sup>2</sup>/V s for devices which organic thin film was deposited at different rates. It is worth noting that the threshold voltage  $U_T$  of about  $-0.1\,\mathrm{V}$  is significantly lower than what has been reported for 6T-based SGOFETs of the same layout  $(U_T \lesssim -0.3 \text{ V})$ . Such a low  $U_T$  might be due to favorable values of, for example,  $C_{dl}$ , the surface charge of the semiconductor or the work function of the DH6T molecules.<sup>33</sup> Above all, it enables the operation of the SGOFETs at low voltages, which is of utmost importance for a good device stability.<sup>8,16,17</sup> To additionally characterize the current onset of the transistors, the subthreshold swing was extracted from a logarithmic plot of the transfer curve (red squares in Figure 3(c)). Its theoretical limit at room temperature is 60 mV/dec. 34 Values as low as 160 mV/dec confirm a fast switching behavior of our devices. The deviation from the theoretical limit may result from defect states at the semiconductor-electrolyte interface or from the chosen device geometry.34

Furthermore, the influence of the morphology of the thin films on the transistor characteristics was studied by evaluating field-effect mobility and subthreshold swing as a function of the substrate temperature during deposition. Figure 3(d) (black dots) illustrates that the best performance was observed at the lowest and highest temperature. This possibly indicates two competing effects: On the one hand, the films are more two-dimensional at low  $T_{sub}$  (cf. Figures 1(a)-1(e)), which enhances charge transport and, thus, the field-effect mobility.<sup>35</sup> On the other hand, the analysis of the structural properties suggests an improved degree of ordering at high  $T_{sub}$ . An increase in structural order has also been reported for  $\alpha,\omega$ -DH6T thin films in comparison to films of  $\beta,\beta'$ -DH6T or unsubstituted 6T, and it has been correlated to an increase in field-effect mobility.<sup>23</sup> Thus, the anew increase in mobility at high  $T_{sub}$  may presumably be attributed to an improvement of the structural order in the film. As Figure 3(d) (red squares) further illustrates, the subthreshold swing confirms this interpretation: a faster on-switching of the SGOFETs (low subthreshold swing values) is enabled by a two-dimensional film morphology (lowest  $T_{sub}$ ) and a high degree of structural order (highest  $T_{sub}$ ). Nevertheless, it has to be noted that the effect of  $T_{sub}$  on the thin film is more pronounced for the increase from room temperature to 43 °C than for the change from 43 °C to 55 °C (cf. Figures 1(a)-1(d)). More data statistics will be needed in order to verify the observed trend in  $\mu$  and in the subthreshold swing (cf. Figure 3(d); see Figure S5 for a visualization of the statistics of  $\mu$  used in this work<sup>26</sup>). From the correlation of the subthreshold swing with both the defect density and the field-effect mobility, it may also be concluded that the good transistor performance is the result of a low defect density.

The capability of the DH6T-based SGOFETs to be applied as sensors in aqueous electrolytes, in this particular case as pH sensors, is demonstrated in Figure 4(a). With decreasing pH of the buffer solution, the transfer curves shift to more negative gate voltages, while  $g_m$  stays unchanged. Therefore, the pH sensitivity is given by the change in gate voltage  $U_G$  per pH with respect to  $U_G$  at neutral pH for a fixed value of the drain-source current  $I_{DS}$ .  $U_G$  experiences a linear dependence over a wide pH range without any hysteresis between decreasing and increasing pH, yielding a sensitivity of 14 mV/pH. According to the amphifunctional model, which is described in detail in the supplementary material,  $^{26}$  the response of the transistor originates from a pHdependent surface charge  $\sigma_{surf}$  at the semiconductorelectrolyte interface.<sup>36</sup> In order to obtain a good match between experimental data and a simulation using the amphifunctional model (blue line in Figure 4(b)), a monolayer coverage with hydroxide ions and an ionizable surface group of  $pK_a$  3.3 have to be assumed. The latter group can be ascribed to oxygen-related moieties. 17 These findings are in agreement with those by Buth et al. for devices using 6T as organic semiconductor. 17

Besides the study of the pH sensitivity, the sensitivity of the devices to changes in the ionic strength was investigated by adding KCl to the solution. In Figure 4(c), the corresponding change in  $U_G$  for a fixed value of  $I_{DS}$  is plotted logarithmically versus the salt activity for two different pH values of the buffer. The ion sensitivity is defined as the slope of the linear fit to the curves at high activity ( $a \gtrsim 50\,\mathrm{mmol/kg}$ ), yielding values of  $-42\,\mathrm{mV/dec}$  at pH 5 and  $-30\,\mathrm{mV/dec}$  at pH 3 for the presented SGOFET. The ion sensitivity has been

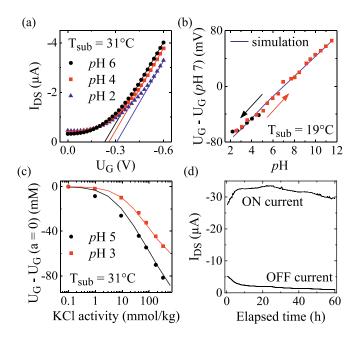


FIG. 4. Sensing and stability properties of SGOFETs. (a) Transfer curves recorded at three different pH values of the KPBS buffer. The solid lines represent fits to the linear regions. (b) Shift of  $U_G$  as a function of the pH of the electrolyte, together with a simulation of the data using the amphifunctional model. (c) Shift of  $U_G$  (compared to  $U_G$  at a salt activity a=0 mM) as a function of the activity of KCl in the PBS buffer, which pH was adjusted to two different values. The solid lines represent simulations of the experimental data using the amphifunctional model. The substrate temperatures at which the DH6T thin films used in (a)–(c) were deposited are indicated in the graphs. (d) Evolution of the drain-source current  $I_{DS}$  during continuous cycling of  $U_G$  between 0 V and -0.6 V for  $U_{DS}=-0.2$  V, measured in 5 mM PBS at pH 5 and in the dark (deposition temperature of the DH6T thin film:  $T_{sub}=31\,^{\circ}$ C). For clarity, only the maxima (ON current) and minima (OFF current) of the measured curve are shown in the graph.

interpreted in terms of the screening of the surface charge due to an increase in the diffuse charge.<sup>37</sup> If the surface charge is more negative, i.e., if the buffer is less acidic, the ion screening is more effective, which is confirmed by the higher sensitivity at pH 5 as compared to pH 3. Using a model similar to the amphifunctional model introduced by Härtl et al.,<sup>37</sup> the experimental data could be reproduced (solid lines in Figure 4(c)) assuming surface charges of  $-5.6\,\mu\text{C/cm}^2$  at pH 5 and  $-3.5\,\mu\text{C/cm}^2$  at pH 3, respectively, in agreement with the calculations by Buth et al. for 6T-SGOFETs.<sup>16</sup>

For applications of organic SGOFETs, the device stability during operation is of vital importance. A stability test was performed by switching on and off the SGOFETs continuously. To this end, the gate voltage was cycled between 0 V and  $-0.6 \,\mathrm{V}$  for approximately 60 h, while applying a constant drain-source voltage of  $-0.2 \,\mathrm{V}$  and recording the drain-source current. Here, the high current level decreased by only 10% with respect to the value after the initial increase in on-current (Figure 4(d)). The latter has been reported before by Roberts et al. for organic field-effect transistors immersed into an aqueous environment. 38,39 However, in contrast to the work by Roberts et al., we observed a slight decrease in the offcurrent over time (see Figure 4(d)). As the transconductance of the respective device increased from  $13 \mu S$  to  $16 \mu S$ throughout the measurement and the subthreshold swing was reduced from about 550 mV/dec to 230 mV/dec, both changes may possibly be attributed to the passivation of trap states at the semiconductor-electrolyte interface by water molecules penetrating into the thin film.<sup>34</sup>

In summary, vacuum-evaporated thin films of the organic semiconductor DH6T were investigated by AFM, XRR, and UV-Vis spectroscopy. We could show that with increasing substrate temperature, the films exhibit an increasingly three-dimensional topography and feature a higher degree of structural order. At the same time, the tilt angle of the molecules towards the substrate surface normal appears to increase. Furthermore, we have fabricated and characterized SGOFETs using these thin films as the active material. The obtained characteristics are comparable to or even exceed those of analogous devices based on 6T. 16,17 In particular, the low threshold voltage is beneficial for a good transistor stability. Field-effect mobility and subthreshold swing were found to be correlated to the morphology and structural order of the films. This implies that the transistor performance can, to some extent, be tuned by the substrate temperature. Additionally, both pH and ion sensitivity of the SGOFETs were demonstrated, and the data could be simulated using suitable modifications of the amphifunctional model. 16,17,36,37 Finally, a good device stability was confirmed by switching it on and off continuously over a period of 60 h. The initial increase in the on-off ratio was tentatively attributed to the passivation of trap states at the semiconductor-electrolyte interface by water molecules. During the period of 60 h, the current level decreased by only 10%. In conclusion, SGOFETs based on DH6T are promising platforms for stable in-electrolyte sensing applications. By carefully choosing the growth parameters of the organic thin film, the performance may possibly be further improved.

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